SCREEN

NEWS RELEASE

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Dainippon Screen Attains Over 60%[*] of Global Market for Single Wafer Spray Cleaning Equipment

Kyoto, Japan -- April 10, 2009 -- Dainippon Screen Mfg. Co., Ltd. led the global market for single wafer spray cleaning equipment[*1] with a 60.3%[*] market share in 2008. With this achievement, Dainippon Screen has attained a share of over 50% of the world market for all the main equipment types that it manufactures for use in cleaning processes for semiconductor production.

Recently, many firms in the semiconductor industry - in particular, R&D consortiums and major logic semiconductor manufacturers - have been faced with the urgent task of developing advanced semiconductor chips for the coming next-generation semiconductor market. This challenge has created an urgent need within the industry for processing technology that can respond to further miniaturization and multilayered wiring without damaging circuit patterns, and removal technology to eliminate contaminants such as minute dust particles and metal impurities. These needs have in turn spurred rapid growth in demand for single wafer spray cleaning equipment used in wafer cleaning processes, which represent about one quarter of all production processes.

Thanks to this demand, Dainippon Screen enjoyed a steady increase in shipments to the US and Taiwan despite the severe recession that is currently gripping the semiconductor industry. The company significantly increased its share of the market for single wafer spray cleaning equipment from 40.6%[*] in 2007 to 60.3%[*] in 2008. Furthermore, Dainippon Screen has attained an overwhelming 57.4% share (up from 50.3% in 2007)[*] of the global market for batch cleaning equipment[*2] and 80.1% (up from 70.7% in 2007)[*] of the market for spin scrubbers[*3], giving the company a majority share of the market for all the main equipment types that it manufactures for use in cleaning processes for semiconductor production. This achievement further strengthens Dainippon Screen's position in the market for semiconductor cleaning equipment.

Dainippon Screen remains committed to providing a varied line of cleaning equipment that meets customer needs and to further strengthening its product competitiveness and service systems, whose excellence is proven by its market share. Moreover, Dainippon Screen intends to further enhance customer satisfaction as it contributes to technical innovation in the semiconductor industry.

*1 Single wafer spray cleaning equipment
Equipment that cleans individual wafers with a chemical spray.
Single wafer spray cleaning equipment processes smaller volumes of wafers than batch cleaning equipment (300 wafers per hour using Dainippon Screen equipment), but provides excellent cleaning performance.

*2 Batch cleaning equipment
Equipment that cleans multiple wafers simultaneously in a chemical bath.
Batch cleaning equipment is capable of processing large volumes of wafers (650 wafers per hour using Dainippon Screen equipment) and is suited to mass production.

*3 Spin scrubbers
Equipment that is used in processes where wafers can be cleaned using only deionized water.
Spin scrubbers clean wafers physically with a soft brush and deionized water.

* Source: "Semiconductor Equipment Market Share Database", Authors: Klaus Rinnen, Dean Freeman, Bob Johnson, Mark Stromberg, Ogawa Takashi and Masatsune Yamaji (Gartner Research, Published on 9 April 2009)
(Revenue from Shipments of Single Wafer Processors, Auto Wet Stations and Scrubbers, Worldwide)